313. PTB Seminar VUV and EUV Metrology

Tuesday, October 22

Time	Speaker	Title	Affiliation
9:00		**Registration & Poster Set-up & Coffee**	
10:00		**Opening remarks**	
10:20		**Session I: EUVL (I)**	Chair: Scholze
10:20	V. Banine	**Keynote: EUV lithography in high volume manufacturing**	ASML
11:00	N. Böwering	Cryogenic cleaning techniques for tin-contaminated EUV lithography optics	U Bielefeld
11:20	P.U. Pennartz	Production challenges and performance of replicated optics for EUV and Soft X-rays	Rigaku ITE
11:40	M. van Putten	EUV Beam Line 2 (EBL2) in commission: operating the EUV optics lifetime test facility	TNO
12:00		Group Photo	
12:20		Lunch Buffet	
13:00		Poster & Coffee	
14:00		**Session II: Materials & Space applications**	Chair: Gottwald
14:00	J. Rebellato	Modeling of the EUV spectral response of the Full Sun Imager aboard Solar Orbiter	CNRS/CNS
14:20	J.I. Larruquert	Spectral evaluation of optical-constant consistency	CSIC IO
14:40	S.A. Garakhin	Broadband stack mirrors for the EUV range: calculation, manufacturing and characterization	IPM RAS
15:00	M. Soman	Calibrating and comparing Teledyne-e2v's ultraviolet image sensor quantum efficiency processes	OU
15:20		Coffee	
16:00		**Session III: Gratings**	Chair: Laubis
16:00	Y. Liu	Diffraction gratings fabricated by dynamic-exposed holography with a phase mask	NSRL/USTC
16:20	J. Probst	A new generation of aberration minimized soft X-ray mirrors and diffraction gratings	NOB
16:40	M. Burkhardt	Adapted Technologies for Customized EUV-gratings	Carl Zeiss Jena
17:00		End of Sessions	
19:00		Get Together & Dinner Buffet	
22:00		**End of Day 1**	

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9:00		**Session IV: EUVL (II)**	Chair: Kolbe
9:00	H. Enkisch	**Keynote: EUV Optics Now and Then**	CZ SMT
9:40	K. Mann	Wavefront metrology and propagation characteristics of extreme UV and soft X-ray sources	LLG
10:00	S. Brose	EUV-LET: Large-area nanopatterning by interference lithography for scientific and industrial research	RWTH TOS
10:20	I. Milov	Damage processes in ruthenium thin films induced by femtosecond laser pulses for a wide range of incident photon energy	U Twente
10:40		Coffee	
11:20		**Session V: Instrumentation**	Chair: Krumrey
11:20	S. Danylyuk	Laboratory-based EUV metrology for scientific and industrial applications	RWTH
11:40	I. Mantouvalou	Optical pump soft X-ray probe NEXAFS spectroscopy using a laser produced plasma source	TU Berlin
12:00	J. Vieker	Compact EUV Source for metrology and irradiation applications	ILT
12:20	A. Biermanns-Föth	Standalone actinic EUV tools supplementing PTB beamline metrology – challenges in measuring extremely low EUV Reflectance	RI
12:40		Lunch Buffet	
13:20		Poster & Coffee	
14:20		**Session VI: EUV Scatterometry**	Chair: Soltwisch
14:20	A. Andrle	Characterization of nanostructures with grazing incidence X-ray flourescence for element sensitive reconstruction	PTB
14:40	N. Farchmin	Bayesian inversion of GIXRF measurements for parameter estimations with uncertainties	PTB
15:00	P. Schneider	A machine learning method for efficient optimization and parameter reconstruction of nano-structures	JCMwave
15:20	I.A. Makhontin	The refined EUVL mask model	IMEC
15:40		Wrap-up and closing remarks	
16:00		**End of the Seminar**	

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